

(12) United States Patent Hirose

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(54) PLASMA PROCESSING APPARATUS

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U.S. Cl. 156/345.44; 156/345.47;

Field of Search 156/345.44, 345.43, 156/345.47; 118/723 E; 204/298.08, 298.34

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Primary Examiner-Thi Dang

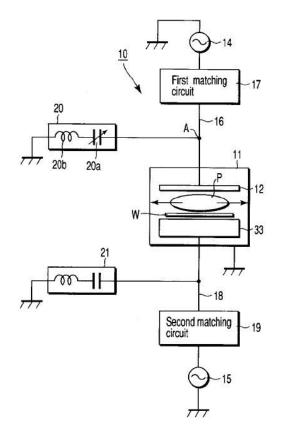
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ABSTRACT

The present invention concerns a plasma processing apparatus for processing a processing object by applying two types of high-frequency power with different frequencies to generate plasma. A first high-frequency line is provided with a first filter circuit for attenuating a high-frequency current from a second high-frequency power supply. A second high-frequency line is provided with a second filter circuit for attenuating a high-frequency current from a first highfrequency power supply. The first filter circuit is provided with a variable capacitor for changing a circuit constant. For changing the circuit constant, the variable capacitor is varied so that a resonance point becomes greater than an optimum resonance point most attenuating a high frequency in the second high-frequency power supply. Doing so decreases a sputter rate of the generated plasma affected on a wall surface of the processing chamber.

7 Claims, 7 Drawing Sheets





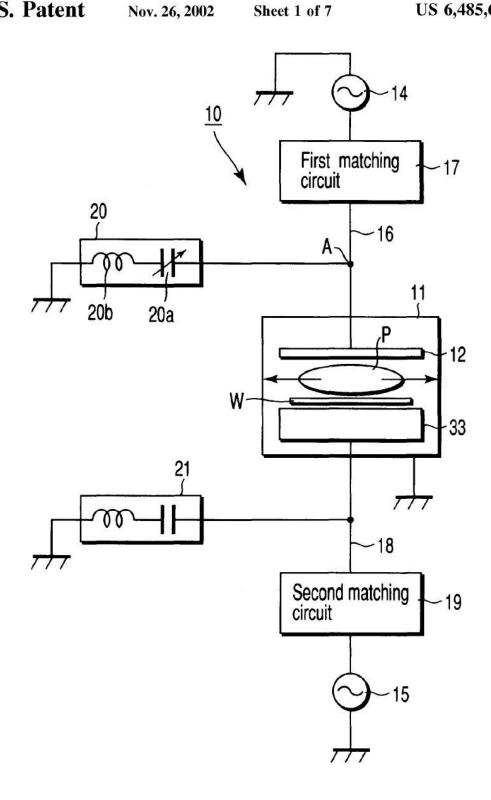
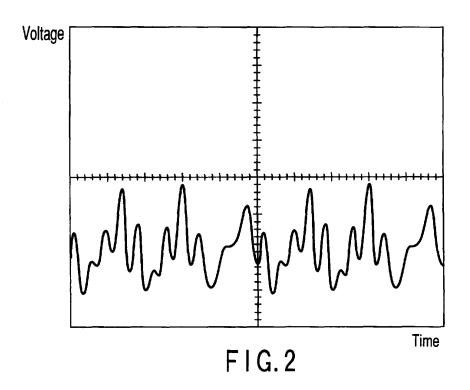
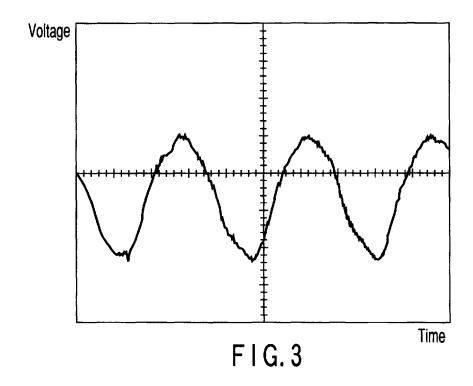
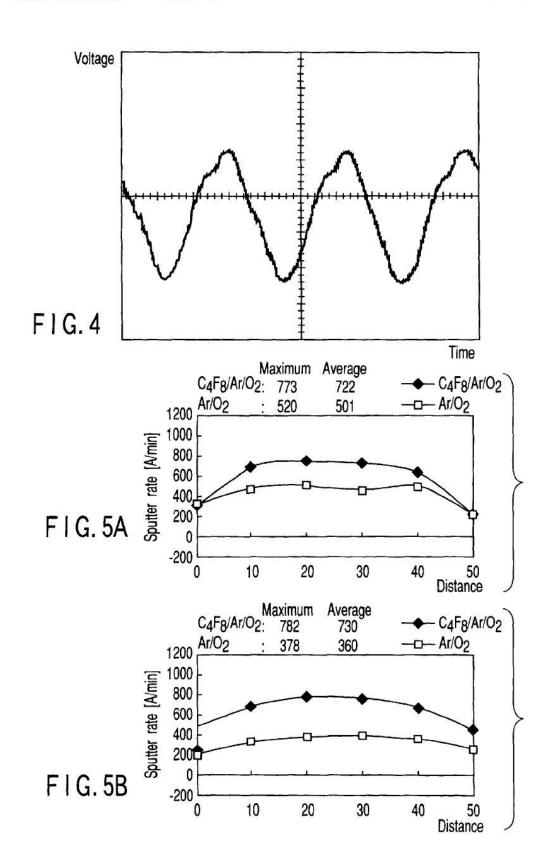


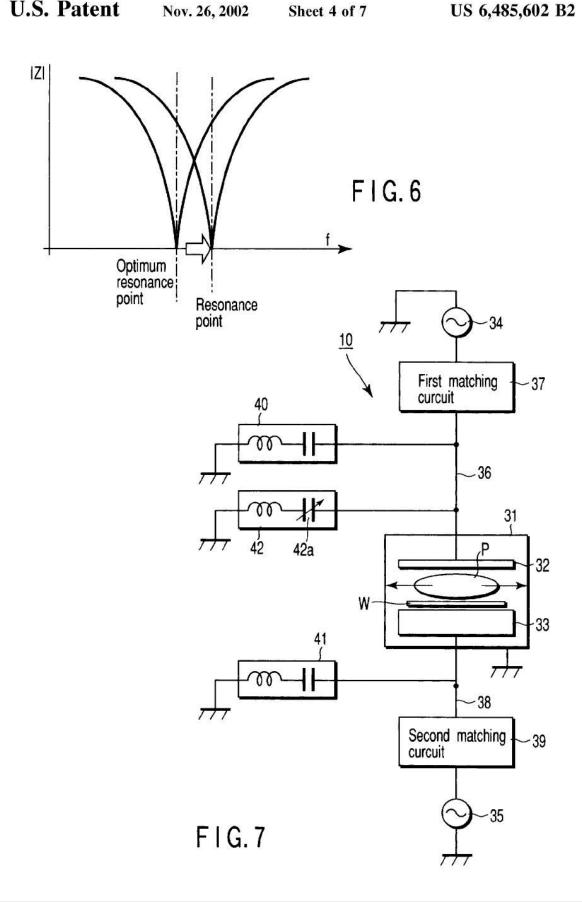
FIG.1











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